			- 01	
	Application No.	Applicant(s)		
Notice of Allowability	09/938,644	RUEGER, NEAL		
	Examiner	Art Unit		
	Anita K Alanko	1765		
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS (ars on the cover sheet with the	correspondence addre	5 5	
herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIG of the Office or upon petition by the applicant. See 37 CFR 1.313	or other appropriate communication GHTS. This application is subject	on will be mailed in due c	ourse. THIS	
1. X This communication is responsive to 11/13/03 and 1/12/04	telephone interview.			
2. ☑ The allowed claim(s) is/are <u>1-66</u> .				
3. The drawings filed on 10 December 2001 are accepted by t	he Examiner.			
 Acknowledgment is made of a claim for foreign priority und a) ☐ All b) ☐ Some* c) ☐ None of the: 	der 35 U.S.C. § 119(a)-(d) or (f).			
 Certified copies of the priority documents have 	been received.			
2. Certified copies of the priority documents have	been received in Application No.	·		
Copies of the certified copies of the priority doc	uments have been received in this	s national stage application	on from the	
International Bureau (PCT Rule 17.2(a)).				
* Certified copies not received:				
 Acknowledgment is made of a claim for domestic priority un reference was included in the first sentence of the specificat 	tion or in an Application Data Shee	sional application) since : et. 37 CFR 1.78.	a specific	
 (a) ☐ The translation of the foreign language provisional ap 6. ☐ Acknowledgment is made of a claim for domestic priority un in the first sentence of the specification or in an Application 	der 35 U.S.C. §§ 120 and/or 121 :	since a specific reference	was included	
Applicant has THREE MONTHS FROM THE "MAILING DATE" of to below. Failure to timely comply will result in ABANDONMENT of the	this communication to file a reply	complying with the requir	ements noted XTENDABLE.	
 A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which gives 	ted. Note the attached EXAMINE reason(s) why the oath or declar	R'S AMENDMENT or NO ration is deficient.	TICE OF	
 CORRECTED DRAWINGS (as "replacement sheets") must (a) ☐ including changes required by the Notice of Draftsperso 	be submitted. on's Patent Drawing Review (PTC	0-948) attached		
1) 🔲 hereto or 2) 🔲 to Paper No	·	•		
(b) \square including changes required by the proposed drawing co	rrection filed, which has b	een approved by the Exa	ıminer.	
(c) \square including changes required by the attached Examiner's				
Identifying indicia such as the application number (see 37 CFR 1.8 each sheet. Replacement sheet(s) should be labeled as such in the	(4(c)) should be written on the draw e margin according to 37 CFR 1.121	ings in the front (not the b	ack) of	
 DEPOSIT OF and/or INFORMATION about the depositation and the depositation of the depositation of the deposit attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF THE DEPOS	it of BIOLOGICAL MATERIAL IE DEPOSIT OF BIOLOGICAL MA	must be submitted. No ATERIAL.	te the	
Attachment(s)				
I ☐ Notice of References Cited (PTO-892)	5☐ Notice of Informal P	atent Application (PTO-1	52)	
Notice of Draftperson's Patent Drawing Review (PTO-948) Information Disclosure Statements (PTO-1449 or PTO/SB/08), Paper No.	6⊠ Interview Summary	6⊠ Interview Summary (PTO-413), Paper No		
	7⊠ Examiner's Amendn	nent/Comment		
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8⊠ Examiner's Stateme 9⊡ Other	nt of Reasons for Allowa	nce	
		Anuta K. SH. Anita K Alanko Primary Examiner Art Unit: 1765	anles	

Application/Control Number: 09/938,644

Art Unit: 1765

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Ryan Flax on January 12, 2004.

The application has been amended as follows:

In the claims:

In claim 1, line 15, after "etching" insert

-- , thereby forming a second contoured feature at said contoured feature --

In claim 8, line 1, delete "Previously amended" and insert - - Previously presented - -

In claim 28, line 8, after "magnetic field" insert

-- , thereby forming a contoured feature at said contoured region --

In claim 32, line 1, delete "Previously amended" and insert - - Previously presented - -

In claim 33, line 1, delete "Previously amended" and insert - - Previously presented - -

In claim 34, line 1, delete "Previously amended" and insert - - Previously presented - -

In claim 35, line 1, delete "Previously amended" and insert - - Previously presented - -

In claim 36, line 1, delete "Previously amended" and insert - - Previously presented - -

Art Unit: 1765

In claim 53, line 7, after "plasma" insert

-- to form a second contour at said at least one contour --

In claim 66, line 12, after "workpiece" insert

-- , thereby forming a contoured feature at a contour of said workpiece --

In claim 66, line 14, after "adjusting", delete the comma.

In the specification:

(not approved in advance by applicant, but requested in response to the first office action on the merits)

on page 8, lines 19 and 25; delete "E" and insert the arrow above the letter -- E --

on page 9, lines 3, 5, 6, 9, 11, 13, 14, 17, 19, delete " β " and insert -- β -- (absolute value indicators, the vertical bars remain, this amendment inserts an arrow above the letter)

on page 10, line 27, page 11, lines 2, 5, 9, 17, delete " β " and insert -- β -- (absolute value indicators, the vertical bars remain, this amendment inserts an arrow above the letter)

The following is an examiner's statement of reasons for allowance: the prior art does not teach or suggest a method of forming a microstructure by micromachining, comprising

providing a substrate in a processing chamber, said substrate comprising an etchable material and having at least one contoured feature,

Application/Control Number: 09/938,644

Art Unit: 1765

generating a stable ion-containing etching plasma in said processing chamber, said plasma etching the contoured feature of said substrate;

generating a magnetic field, said magnetic field being adjustable in intensity and direction;

applying an RF bias power to said substrate, said RF bias power being adjustable in intensity; and

controlling said etching of the contoured feature by creating an electron differential at said contoured feature by adjusting at least one of said magnetic field intensity, magnetic field direction, and RF bias power intensity during said etching, thereby forming a second contoured feature at said contoured feature, as in the context of claim 1.

The closest prior art, Moslehi, discloses etching of contours, but does not suggest to form a second contour at said first contour (as shown, for example in Figures 9-12A) by adjusting the magnetic field intensity, direction or RF bias power intensity during said etching, as in the context of claim 1.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Art Unit: 1765

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Anita K Alanko whose telephone number is 571-272-1458. The examiner can normally be reached on Mon, Tues & Fri: 8:30 am-5 pm; Wed&Thurs:10 am-2 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 872-9306 for regular communications and (703) 872-9306 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0661.

Anita K Alanko Primary Examiner

Arita K. Alamba

Art Unit 1765